

BEAMeeting Stuttgart 2024

Wednesday, April 10th, 2024

Training Jörg Günther / Jing Becker	Session 1: BEAMER – Layout Operation and Fracturing*	9:00
	Coffee Break	10:30
Training Jörg Günther / Dmitri Titko / Daniel Ritter / Anirudh Peyyety	Session 2: Proximity & Process Calibration and Correction* ProSEM Workshop and Training*	10:45
	Lunch Break	12:00
Nezih Ünal / Uli Hofmann GenISys	Welcome & GenISys Update	13:00
Julian Hartbaum IMS	Introduction IMS Chips	13:20
Markus Greul IMS	Optimizing chemically amplified photoresist processes in electron beam lithography	13:30
Jan Klikovits GenISys	TRACER calibration for chemically amplified photoresists	14:00
Kevin Anthony Hofhuis Paul Scherrer Institut	Grayscale lithography in HSQ and the application of dose gradient shapes	14:20
	Coffee Break & IMS Tour	14:40
Dr. Cathelijan van Nisselroy Heidelberg Instruments Nano AG	Towards automation and parallelization in thermal scanning probe lithography with the NanoFrazor	15:30
Anirudh Peyyety GenISys	Application Use Cases of ProSEM	16:00
Sven Bauerdick GenISys	Automated Layout-based SEM Metrology with ProSEM and InSPEC Discussion MIS	16:30
	Closing	17:30
Relaxa Waldhotel Schatten Stuttgart	Champagne reception	18:00
	Dinner	19:00
Thursday, April 11th, 2024		
Jing Becker GenISys	Loops, Variables, Functions	9:00
Holger Sailer IMS	Resolution optimization optical lithography	9:30
Nadia Chahir University of Twente	Proximity effect correction for e-Beam fabrication of Aluminum Oxide waveguides	10:00
	Coffee Break	10:30
Jürgen Weis MPI	Nanostructuring Lab at the MPI for Solid State Research	11:00
Thomas Michels GenISys	BEAMER Update Development Roadmap and Discussion	11:30
Max-Planck-Institut	MPI Tour	12:00
Max-Planck-Institut Cafeteria	Lunch at MPI	13:15
	Open Discussion and User Workshops* With Coffee	14:00
	Closing	16:30

* only on-site